

Amendments to the Specification:

Please add the following new paragraph immediately after the title, on page 1:

This application is a continuation of, and claims priority under 35 U.S.C. 120 to, U.S. Patent Application Serial No. 09/993,090, filed November 6, 2001. This application also claims the benefit of Japanese Patent Application No. 2000-338460, filed November 7, 2000.

Replace the paragraph beginning on page 23, line 12, with the following amended paragraph:

The thus-obtained solution of the photosensitive composition for sandblasting was applied to a 20  $\mu\text{m}$ -thick polyethylene terephthalate film (PET film) in a dry coating thickness of 30  $\mu\text{m}$  using an applicator, followed by drying to form a photosensitive composition layer. Subsequently, a 20  $\mu\text{m}$ -thick polyethylene film was adhered onto the photosensitive composition layer under a rubber roller taking care of not entrapping air bubbles, thus a ~~photosensitive~~ photosensitive film for sandblasting being obtained.

Replace the paragraph beginning on page 24, line 9, with the following amended paragraph:

Next, resistance of the pattern to sandblasting was evaluated as follows. The polyethylene film was stripped off, and the bare photosensitive composition layer was laminated on a glass substrate preheated to 80 °C by means of a rubber roller, the PET film was then stripped off, and the entire surface of the photosensitive composition layer was exposed to light emitted from an ultrahigh-pressure mercury lamp at an irradiation amount of 150 mJ/cm<sup>2</sup> and subjected to sandblasting with an abrasive of glass beads #800 (produced by Alps Engineering) at a blasting pressure of  $1.96 \times 10^5$  Pa (2.0 kgf/cm<sup>2</sup>) from a sandblast nozzle located at a distance of 80 mm. The time required for the cured resin layer to disappear by abrasive wear was ~~measured~~ measured to be 150 seconds, which shows a good sandblasting resistance.